

IMiD 2024

The 24th International Meeting on Information Display
August 20-23, 2024 / ICC Jeju, Jeju, Korea

Session Title:	03. Semiconductor Materials and Processing for High Performance TFTs
Session Date:	August 21 (Wed.), 2024
Session Time:	09:00-10:20
Session Room:	Room C (Samda)

[C03-1] [Invited] 09:00-09:25

High-Mobility and Enhancement-Mode Thin-Film Transistors with Solid-Phase Crystallized Hydrogen-Doped Polycrystalline Indium Oxide Channel

Mamoru Furuta, Xiaoqian Wang, Naoki Okamoto, Kotaro Morita (Kochi Univ. of Tech., Japan), and Yusaku Magari (Hokkaido Univ., Japan)

[C03-2] [Invited] 09:25-09:50

High Performance Oxide TFTs Deposited by ALD Method

Takanori Takahashi and Yukiharu Uraoka (Nara Inst. of Science and Tech., Japan)

[C03-3] 09:50-10:05

Low Voltage Solution Processed α -Ga₂O_x Thin-Film Transistor Using Bilayer High-k Al₂O₃ and HfO₂ Gate Insulator

Dian Budiarti Kastian, Juan Paolo S. Bermundo, and Yukiharu Uraoka (Nara Inst. of Science and Tech., Japan)

[C03-4] 10:05-10:20

High-Performance Oxide Transistor Induced by a Metal Capping Layer on the Active Layer with Controlled Hydrogen Content

Ji-Min Park (Dongguk Univ., Korea), Minju Song, Junghwan Kim (UNIST, Korea), and Hyun-Suk Kim (Dongguk Univ., Korea)